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				APPLICANT: Yvon GRIS et al.			
				GROUP ART UNIT: 1765		EXAMINER: Unassigned	
Sheet	1	Of	1				

#### U.S. PATENT DOCUMENTS

Examiner's Initials#	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication or of issue of Cited Document MM-DD-YYY
		Number	Kind Code		
MS		5,010,034		Manoliu	04/23/91
MS		5,554,561		Plumton	09/10/96

#### FOREIGN PATENT DOCUMENTS

Examiner's Initials#	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document (not necessary)	Date of Publication of Cited Document MM-DD-YYYY	Translation (Y/N)
		Office/Country	Number	Kind Code			
MS		EP	0 746 032	A	Matsushita Electronics Corp.	12/04/96	Y
MS		EP	0 813 232	A	NEC Corp.	12/17/97	Y

#### OTHER ART — NON PATENT LITERATURE DOCUMENTS

Examiner's Initials#	Cite No	Include name of the author (in CAPITAL LETTERS) title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, relevant page(s), volume-issue number(s), publisher, city and/or country where published.	Translation (Y/N)	
MS		French Search Report from French Patent Application 98 01313, filed January 30, 1998	Y	
		Patent Abstracts of Japan, vol. 007, no. 243 (E-207), October 28, 1983 & JP-A-58 131748 (Fujitsu KK)	Y	
		Patent Abstracts of Japan, vol. 095, no. 010, November 30, 1995 & JP-A-07 176742 (NEC Corp.)	Y	
		Garverick L.M., et al.: "Silicon Surface Cleaning By Low Dose Argon-ion Bombardment For Low Temperature (750 C) Epitaxial Deposition. II. Epitaxial Quality" Journal Of Applied Physics, vol. 62, no. 8, October 15, 1987, pp 3398-3404	Y	
		Patent Abstracts of Japan, vol. 013, no. 541 (E-854), December 5, 1989 & JP-A-01 223765 (NEC Corp.)	Y	

EXAMINER <i>Matthew Song</i>	DATE CONSIDERED 1/15/02
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#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.